

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ASMMC.052AUS	APPLICATION NO. 10/719,277
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT Elers	
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE November 20, 2003	GROUP 2811



U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS
<i>W</i>	1	4,450,472	5/22/84	Tuckerman et al.		
	2	4,938,742	7/3/90	Smits		
	3	5,218,515	6/8/93	Bernhardt		
	4	5,241,450	8/31/93	Bernhardt et al.		
	5	5,461,003	10/24/95	Havemann et al.		
	6	5,619,177	4/8/97	Johnson et al.		
	7	5,777,292	7/7/98	Grigorov et al.		
	8	5,901,037	5/4/99	Hamilton et al.		
	9	5,936,295	8/10/99	Havemann et al.		
	10	6,060,383	5/9/00	Nogami et al.		
	11	6,272,169 B1	8/7/01	Boswell, Jr. et al.		
	12	6,482,733	11/19/02	Raaijmakers et al.		
	13	6,534,395	3/18/03	Werkhoven et al.		
	14	6,629,425	10/7/03	Vaiyapuri et al.		
	15	6,686,271	2/3/04	Raaijmakers et al.		
	16	6,699,783	3/2/04	Raaijmakers et al.		
	17	6,703,708	3/9/04	Werkhoven et al.		
	18	6,727,169	4/27/04	Raaijmakers et al.		12/15/03
<i>W</i>	19	US 2003/0032281 A1	2/13/03	Werkhoven et al.		
<i>W</i>	20	US 2003/0143839 A1	7/31/03	Raaijmakers et al.		11/22/02

FOREIGN PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS
					TRANSLATION	
					YES	NO
<i>W</i>	21	WO 98/03996	1/29/98	PCT		
<i>W</i>	22	WO 98/03997	1/29/98	PCT		
<i>W</i>	23	WO 98/04109	1/29/98	PCT		
<i>W</i>	24	WO 03/053895 A2	7/3/03	PCT		

EXAMINER	<i>K. R. L. M. S. A. T.</i>	DATE CONSIDERED	<i>6/19/03</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.			

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EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
WR	25 Blackburn, J.M. et al., "Deposition of conformal copper and nickel films from supercritical carbon dioxide," Science 294(5540) (2001) pp. 141-145
~	26 Cabanas, A. et al., "Alcohol-Assisted Deposition of Copper Films from Supercritical Carbon Dioxide," J. Chemistry of Materials 15(15) (2003) pp. 2910-2916
✓	27 Dagani, Ron, "Dry Spinning of Carbon Nanotube Yarns"
✓	28 Kondoh, E. et al., "Characteristics of copper deposition in a supercritical CO <sub>2</sub> fluid," Microelectronic Engineering 64(1-4) (2002) pp. 495-499
✓	29 Lesiak, B. et al., "Characterization of Polyacetylene and Polyacetylene Doped with Palladium," Polish J. Chem., 74:847-865 (2000)
✓	30 J.-Q. Lü et al., Advanced Metallization Conference 2000 (ULSI XVI), pp. 515-521.
✓	31 Shirakawa, Hideki et al., "Synthesis of Electrically Conducting Organic Polymers: Halogen Derivatives of Polyacetylene, (CH),," J.C.S., Chem. Comm., 578-580 (1977)
WR	32 Tay, Andrew A.O., "Analytical Study on A MEMS Micro-Cooling System for Cooling of Flip Chips," Conf. on Design, Characterization, and Packaging for MEMS and Microelectronics, Queensland, Australia, Oct. 99, SPIE Vol. 3893, pp. 82-93
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EXAMINER <i>H. L. Casper</i>	DATE CONSIDERED <i>1/9/05</i>
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